

Claims:

What is claimed is:

1. A masking mechanism for a film forming apparatus, characterized in that:

it comprises a single mask and a means for moving the mask relative to a substrate in a uniaxial direction; and

said mask has a first, a second and a third single action edge each of which has a normal unit vector; wherein:

the normal unit vector of said first single action edge and that of said second single action edge make an angle of  $120^\circ$  relative to each other, the normal unit vector of said second single action edge and that of said third single action edge make an angle of  $120^\circ$  relative to each other, and the normal unit vector of said third single action edge and that of said first single action edge make an angle of  $120^\circ$  relative to each other.

2. A masking mechanism for a film forming apparatus as set forth in claim 1, characterized in that:

said mask has a side making an angle of  $90^\circ + \alpha$  (where  $0^\circ \leq \alpha < 90^\circ$ ) relative to said uniaxial direction, and

said mask has a first and a second opening, wherein

said first opening has a side making an angle of  $30^\circ + \alpha$  relative to said uniaxial direction and said second opening has a side making an angle of  $-30^\circ + \alpha$  relative to said uniaxial direction, and

said side making an angle of  $90^\circ + \alpha$  relative to said uniaxial direction constitutes said first single action edge, said side making an angle of  $30^\circ + \alpha$  relative to said uniaxial direction constitutes said second single action edge, and said side making an angle of  $-30^\circ + \alpha$  relative to said uniaxial direction constitutes said third single action edge.

3. A masking mechanism for a film forming apparatus as set forth in claim 1, characterized in that:

said single mask comprises a single disk having a first, a

second and a third cutouts, and

said first cutout has a side making an angle of  $90^\circ + \alpha$  (where  $0^\circ \leq \alpha < 90^\circ$ ) relative to a circumferential direction of said disk, said second cutout has a side making an angle of  $30^\circ + \alpha$  relative to the circumferential direction, and said third cutout has a side making an angle of  $-30^\circ + \alpha$  relative to said circumferential direction, wherein

said side making an angle of  $90^\circ + \alpha$  relative to said circumferential direction of said mask constitutes said first single action edge, said side making an angle of  $30^\circ + \alpha$  relative to said circumferential direction constitutes said second single action edge, and said side making an angle of  $-30^\circ + \alpha$  relative to said circumferential direction constitutes said third single action edge.

4. A masking mechanism for a film forming apparatus, characterized in that:

it comprises a single mask and a means for moving the mask relative to a substrate in a uniaxial direction; and

said mask has a first and a second single action edge each of which has a normal unit vector and a double action edge in the form of a triangle having its base oriented in said uniaxial direction and its two other sides constituting action edges, wherein

the normal unit vector of said first single action edge makes an angle of  $30^\circ$  relative to said uniaxial direction and the normal unit vector of said second single action edge makes  $-30^\circ$  relative to said uniaxial direction.

5. A masking mechanism for a film forming apparatus as set forth in claim 4, characterized in that

said single mask comprises a single disk having a first and a second cutout, and

said first cutout is a cutout in the form of a fan having its two sides making angles of  $30^\circ$  and  $-30^\circ$  relative to a circumferential direction of said disk, respectively, and said second cutout is a cutout having sides making angles of  $60^\circ$  and  $-60^\circ$  relative to the

circumferential direction of said disk and a side oriented parallel to said circumferential direction.

6. A masking mechanism for a film forming apparatus, characterized in that:

it comprises a single mask and a means for moving the mask relative to a substrate in a uniaxial direction; and

said mask has a triangular opening having a base side oriented in a said uniaxial direction, said mask also having a side extending orthogonal to said uniaxial direction; and

the other two sides other than the base side of said triangular opening and said side orthogonal to said uniaxial direction constitute a triple action edge, whereby

selecting a rate of movement at which said triangular opening is moved and a rate of movement at which said side orthogonal to said uniaxial direction allows a film thickness gradient to be produced in a particular direction determined by the rates of movement selected.

7. A masking mechanism for a film forming apparatus as set forth in claim 6, characterized in that

said single mask is a single disk;

said disk has a first cutout, and a second cutout or a first opening;

said first cutout is a fan shaped cutout, said second cutout is a cutout having a side extending orthogonal to a circumferential direction of said disk, and said first opening is a triangular opening having a base side extending parallel to a circumferential direction of said disk; and

the two sides of said fan shaped cutout and the side of said second cutout that extends orthogonal to a circumferential direction of said disk constitutes said triple action edge, or the two sides of said triangular opening other than said base side and the side of said second cutout that extends orthogonal to a circumferential direction of said disk constitutes said triple action edge.